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METHOD AND SYSTEM FOR CALIBRATING THE SCAN
AMPLITUDE OF AN ELECTRON BEAM LITHOGRAPHY INSTRUMENT

5 ABSTRACT OF THE DISCLOSURE

10 A method for calibrating the scan amplitude of an
electron beam lithography instrument by determining the
position of a feature within the scan. The method is
effective at the operating frequency of the scan and
using a limited bandwidth video signal including the
steps of determining the reference feature to be an
edge over which the video signal rises abruptly from a
background level to a white level. The method turns the
beam on only over a short region of the scan and
15 represents the degree of overlap between the beam on
portion of the scan and the white part of the feature
as the total video signal accumulated in that scan.

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